

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5165	(mask same writ\$4) and (design same data)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L2	308	(mask same writ\$4) and (design same data) and layer and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:00
L3	241	(mask same writ\$4) and (design same data) and layer and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L4	415	(mask same writ\$4) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L5	223	(mask same writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L6	192	(mask near6 writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L7	1393	(mask near6 writ\$4) and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L8	103	(mask same writ\$4) and (design same data) and layer and opc and feature and context	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53

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L9	41	(mask same writ\$4) and (design same data) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L10	75	(mask near6 writ\$4) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L11	65	(mask same writ\$4) and (design same data) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L12	74	(mask same writ\$4) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L13	180	(mask near6 writ\$4) and opc and print and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L14	319	(mask near6 writ\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L15	103	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L16	18	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53

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L17	21	(mask same lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L18	22	(mask same lithograph\$3) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L19	18	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L20	49	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and writ\$3 and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L21	47	(mask near6 writ\$4) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L22	47	(mask near6 writ\$4) and (multiple same layer) and print and writ\$3 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 09:53
L23	527	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:01
L24	464	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:01

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L25	395	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and context	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:02
L26	174	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and context and distortion	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:02
L27	173	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and context and distortion and factor and parameter	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:08
L28	1	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and context and distortion and factor and parameter and ("716"/\$.ccls or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:04
L29	27	(mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and (context same circuit) and distortion and factor and parameter	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:10
L30	0	((mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and (context same circuit) and distortion and factor and parameter).CLM.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:10

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» Key

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IET JNL IET Journal or Magazine

IEEE CNF IEEE Conference Proceeding

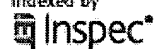
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L30	0	((mask same writ\$4) and (design same data) and layer and priorit\$3 and order\$3 and tolerance and configur\$3 and (context same circuit) and distortion and factor and parameter).CLM.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/01 10:10